

Supplementary information

Dynamic behaviours of epoxy resin thin films during the curing process

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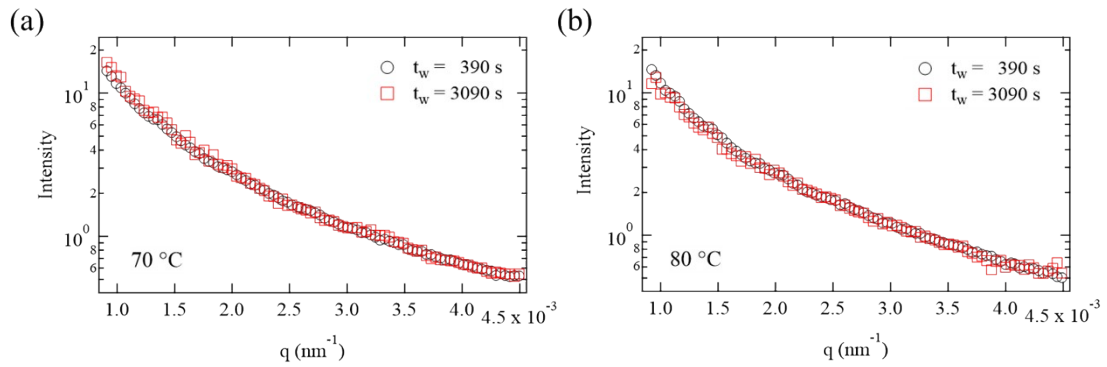


Figure S1. Scattering intensity profiles of the thin films obtained from the initial 100 images ($t_w=390$ s) and the last 100 images ($t_w=3090$ s) at 70 (a) and 80 C (b). No significant change in the scattering profiles depending on t_w were observed.

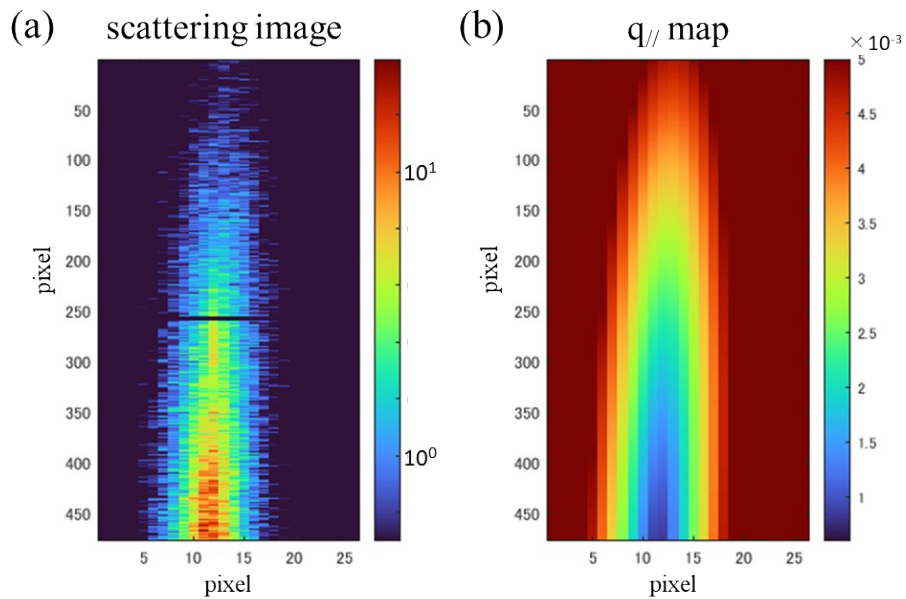


Figure S2. Two-dimensional profiles of scattering intensity obtained from the GI-XPCS measurement at 70 C for representative data (a), and the inplane component of the scattered wave vector ($q_{//}$) (b).